

FIG. 1



<u>200</u>

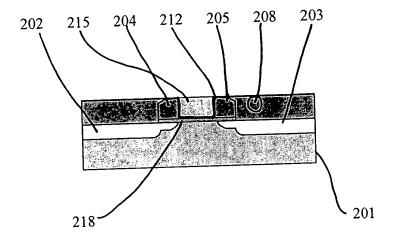


FIG. 2



<u>300</u>

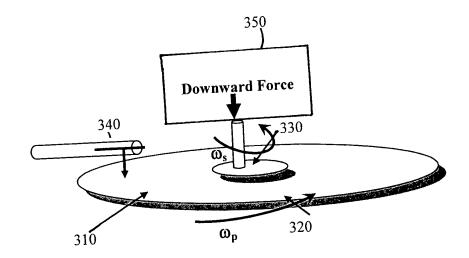


FIG. 3



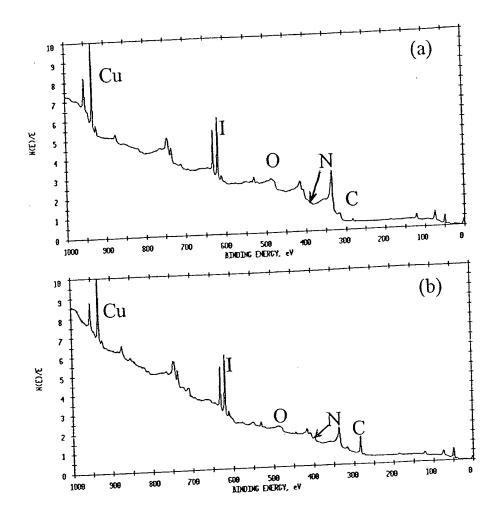
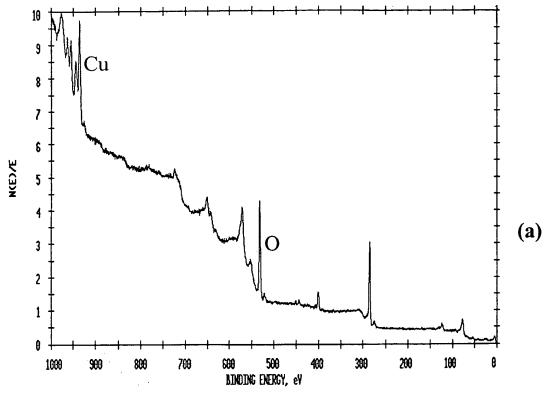


FIG. 4

FIG. 5

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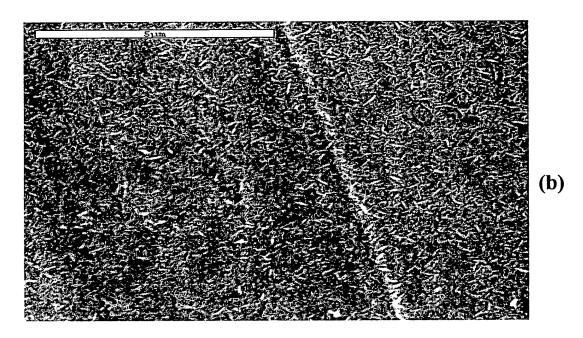


FIG. 6



	Concentration of iodine (N)				
	0.001	0.01	0.1		
Removal Rate (nm/min)	53	775.0	2716		
Selectivity with Cu/Ta	530	>4500	>5000		
RMS (nm)	1.06	1.98	2.13		
Scratches #/cm ²	< 5	<5	<5		

FIG. 7



	Concentration of Hydrogen Peroxide (%)				
	0.1%	1%	10%		
Removal Rate (nm/min)	5	27	6		
RMS (nm)	4.2	5.1	-		

FIG. 8





Pressure	2.7 psi	4.3 psi	6.7 psi
Removal Rate (nm/min)	298	335	425
Selectivity Cu/Ta	>3000	>3000	>3000
Surface Roughness (nm)	1.06	1.4	2.0
Scratches (#cm²)	< 5	< 5	< 5

FIG. 9



0.01 N iodine					
pH 4	pH 6	pH 8	pH 10	pH 12	
1210	909	1023	756	23	
4000	>4000	>4000	>3000	>200	
		pH 4 pH 6	pH 4 pH 6 pH 8 1210 909 1023	pH 4 pH 6 pH 8 pH 10 1210 909 1023 756	

FIG. 10



	Concentration of Particles				
	No particle	1 wt.%	5 wt.%		
Removal Rate (nm/min)	71	114	151		
Selectivity	>1000	> 200	>200		

FIG. 11



effect of small amount of sili	ca in iodine based Cor	ncentration of si	ica particle	
	No particle	0.01 wt.%	0.1 wt.%	1 wt%
	50.4	80.2	153.6	333.5
Removal Rate (nm/min)	7200	529	13	8.0
Selectivity on Cu/Ta Scratches (#/cm²)	0	0	1-2	5



The effect of inhibitors in iodine solution (pH 4 and 2.7 psi)

The effect of inhi	The effect of inhibitors in iodine solution (pH 4 and 2.7 psi)									
The effect of	0.01 N I ₂									
	No		BTA			TTA				
	No inhibitor	1 mM	5 mM	10 mM	1 mM	5 mM	10 mM			
		1 IIIVI 3 IIIVI	 		100.1	106.9	51.8			
Removal Rate	775.0	945.1	56.3	58.4	100.1	100.5				
(nm/min)				1.60	27.2	13.2	7.3			
STD	7.6	14.9	16.6	16.2	21.2	10.2	<u></u>			

The effect of surfactants on removal rate (nm/min) of copper in iodine solution (pH 4 and 6.7 psi)

					10 mN	$\mathbf{I_2}$				
		SAS Trit					Triton	X-100		
	No inhibitor	5-24	2 mM	5 mM	10mM	20 mM	1 mM	2 mM	3 mM	5 mM
		.5 mM		975.7	524.7	514.0	977.5	189.0	129.7	29.5
RR	1210.0	1080.9	1040.0	9/3.7	J24.1					
(nm/min)		55.1	11.6	62.5	34.1	11.5	43.4	30.4	21.2	24.2
STD	33.5	55.1	11.0	1 02.5	<u> </u>					

The static removal rate (nm/min) of copper in iodine based solutions (pH 4)

The etetic	removal i	rate (nm/min) of copper	in iodine based solutions (p	oH 4)						
ne static	Temoval	1010 (3332	10 mN iodine							
	-	No additive	10 mM SAS							
т		64.9 ± 2.65	2.8 ± 0.4	39.6 ± 4.3						
	4		1.1 ± 0.4	65.2 ± 10.1						
pН	6	63.4 ± 2.37	-1.4 ± 0.7	28.9 ± 0.4						
	8	8 48.7 ± 2.4		27.7 ± 0.4						
	9	35.2 ± 1.3	-0.3 ± 0.5	2						



	0.01 N I ₂ , 10 mM TTA					
	No salt	No salt KI			,CI	
		0.001 M	0.01 M	0.01 M	0.1 M	
Removal Rate (nm/min)	52	66	92	34	32	

FIG. 14



Effect of succinic acid/citric acid added in 10 mN Iodine and 5 mM BTA/TTA on CMP

performance

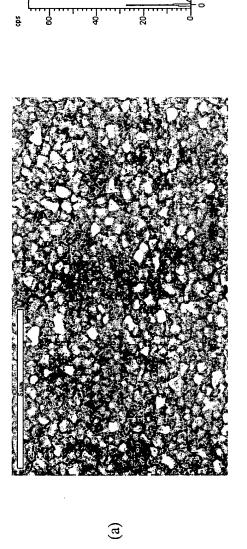
periormanee						
	$10^{-2} \text{ N I}_2,$	5 mM BTA	10^{-2} N I_2	5 mM TTA	10^{-2} N I_2 , 5 mM BTA	
	Succinic Acid		Succi	nic Acid	Citric Acid	
	0.1 M	0.2 M	0.1 M	0.2M	0.1 M	0.2 M
Removal Rate (nm/min)	33.5	37.4	36.6	47.0	295.1	432.5
STD	12.5	1.9	10.9	6.1	26.6	5.0
SRR (nm/min)	3.2	3.9	2.7	3.1	11.7	18.3

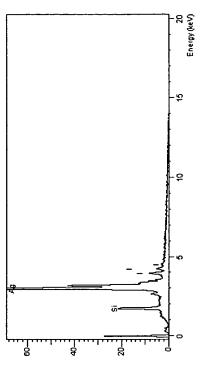
FIG. 15

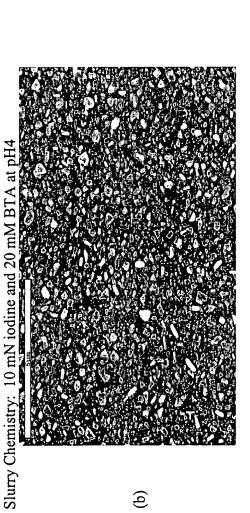


SEM (x10k) pictures and ES of AgI

Slurry chemistry: 10 mN iodine at pH4







(P)

20 Energy (keV)

FIG. 16

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